# Matlab minority carriers documentation What does the app do?

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The analysis of time-resolved photoluminescence lifetime data as a function of temperature is needed in order to understand the dominant recombination mechanisms of a material. This will give evidence of device performance, and can suggest whether material growth quality can improve. Here, a MATLAB application is created which allows for further analysis of lifetime results and it's subroutines are discussed. The format of the documentation will be closer to article-style, to allow for reference in future manuscript drafting. A walkthrough of the MATLAB application will be provided in a powerpoint format to understand the proper buttons that need to be pushed for data analysis.

Usage: The documentation will allow for quick and easy reference for understanding the MATLAB app, and will provide for discussion of recombination mechanisms and formulas used to model the lifetime.

#### INTRODUCTION: MOTIVATION

The mechanisms that are attributed to the minority carrier lifetime contain multiple components. Understanding the constituents that make up the lifetime character of a sample provides evidence of device performance. For background limited performance (BLIP), the photon generation rate per unit area needs to be greater than the thermal generation rate per unit area,[1] or

$$\boxed{\eta_a \Phi_B} > \frac{n_{th} t}{\tau},$$
(1)

where  $\eta_a$  is the absorption efficiency,  $\Phi_B$  the background flux,  $n_{\rm th}$ , t, and  $\tau$  are the density of thermal carriers, thickness of the material and lifetime of the carriers, respectively. For best performance, the lifetime needs to be at a maximum. The minority carrier lifetime will be considered here because the material system of interest are direct band gap materials.

## II. DATA ANALYSIS

The minority carrier lifetime can be characterized by it's recombination mechanisms,

$$\frac{1}{\tau_{tot}} = \frac{1}{\tau_{SRH}} + \frac{1}{\gamma \tau_{rad}} + \frac{1}{\tau_{Auger}},\tag{2}$$

where  $\tau_{SRH}$  is the Shockley-Read-Hall (SRH) lifetime,  $\gamma$  the photon recycling factor,  $\tau_{rad}$  the radiative lifetime and  $\tau_{Auger}$  is the Auger lifetime. The lifetime components are added as recombination rates in order to calculate the total lifetime, which is why the reciprocals are added in Eq. 2.

#### Shockley-Read-Hall Recombination

The recombination of photoexcited carriers with defects in a material is the SRH recombination mechanism. This is observed because there are defect levels,  $E_t$  that occur within the forbidden band gap of a material. The lifetime due to SRH recombination is [2, 3]

$$\tau_{SRH} = \frac{\tau_{p0}(n_0 + n_1) + \tau_{n0}(p_0 + p_1)}{n_0 + p_0}.$$
 (3)

In the case of an n-type sample, and approximating with Boltzmann statistics and parabolic bands[4] we can define the quantities in Eq. 3 by

$$n_0 - p_0 = D \tag{4}$$

$$n_0 p_0 = n_i^2 = N_c N_v \exp(-E_g/kT)$$
 (5)

$$\Rightarrow n_0 = \frac{1}{2} \left( \sqrt{D^2 + 4n_i^2} + D \right) \tag{6}$$

$$n_1 = N_c \exp\left(E_t - E_c\right) / kT \tag{7}$$

$$N_{c} = \frac{1}{4} \left( \frac{2m_{e}^{*}kT}{\pi\hbar^{2}} \right)^{3/2}$$

$$\tau_{p0} = \frac{1}{\sigma_{p}v_{th}N_{t}}$$
(8)

$$\tau_{p0} = \frac{1}{\sigma_p v_{th} N_t} \tag{9}$$

$$v_{th} = \sqrt{\frac{8kT}{\pi m^*}} \tag{10}$$

where D is the doping concentration,  $n_0$  is the concentration of electrons in thermal equilibrium,  $n_1$  is the density of electrons for the case of the fermi level falling at the trap level  $E_t$ ,  $N_c$  is the effective electron density of states,  $\tau_{p0}$  is the lifetime for holes injected in a p-type sample, and  $v_{th}$  is the thermal velocity. The quantities  $\tau_{n0}, p_0, p_1$ , etc. can be found by similar equations and through the relation  $p_0 = n_i^2/n_0$ . When analyzing the total lifetime, the doping D, trap level  $E_t$ , and the product  $\sigma N_t$  are fit parameters to the data. In the case of degenerate materials, such as highly doped materials, metals or

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materials with a negative band gap, Fermi-Dirac statistics will need to be considered. This then causes the approximation of the right hand side of Eq. 5 to become invalid.

## B. Radiative Recombination

Photoexcited carriers in the conduction band recombine with vacancies in the valence band and release the excess energy in the form of a photon, we can model the radiative lifetime through the thermal generation rate introduced by Van Roosbroeck and Shockley,[5]

$$G_R = \frac{8\pi}{h^3 c^2} \int_0^\infty \frac{\epsilon(E)\alpha(E)E^2 dE}{\exp(E/kT) - 1},$$
(11)

where  $\epsilon$  is the relative diffectric constant which is typically approximated by the static dielectric constant taken at energies below the fundamental absorption edge,  $\epsilon_{\infty}$ ,  $\alpha$  is the absorption coefficient, and E is the photon energy. The integral can be integrated numerically with indirect experiments [6] of the absorption coefficient, such as transmission. Another method is through simulation [7, 8] by using a 14 band k.p. theory software. [9] Here, we will compute the integral by giving an approximate analytic form of the absorption coefficient, where the same method was used on analyzing the radiative lifetime on Ge[10] and HgCdTe[11–13] material systems. The analytic form of the absorption coefficient is

$$\alpha_{direct} = \frac{2^{3/2}}{3\epsilon_{\infty}^{1/2}} \frac{m_0 e^2}{\hbar^2} \left[ \frac{m_e^* m_h^*}{m_0 (m_e^* + m_h^*)} \right]^{3/2} \left( 1 + \frac{m_0}{m_e^*} + \frac{m_0}{m_h^*} \right) \times \left( \frac{E - E_g}{m_0 c^2} \right)^{1/2}, \tag{12}$$

where  $m_0$  is the free electron rest mass,  $m_e^*$  is the conduction electron effective mass,  $m_h^*$  is the valence heavy hole effective mass, and  $E_g$  is the material band gap. Inserting this in Eq. 11, we have

$$G_R = n_i^2 5.8 \times 10^{-13} \epsilon_{\infty}^{1/2} \left( \frac{m_0}{m_e^* + m_h^*} \right)^{1/2} \left( 1 + \frac{m_0}{m_e^*} + \frac{m_0}{m_h^*} \right) \times \left( \frac{300}{T} \right)^{3/2} \left( E_g^2 + 3kT E_g + 3.75(kT)^2 \right). \tag{13}$$

The effective masses used for the group III-V material systems will be the effective masses of the major consitutents. For example, for an InAs<sub>0.91</sub>Sb<sub>0.09</sub> alloy, the effective mass[14] and static dielectric constant of bulk InAs[15] will be used.

The radiative generation rate developed in Eq.13 is valid for the internal radiative generation and in a doped sample the internal radiative lifetime becomes

$$\tau_{rad} = \frac{n_i^2}{G_R(n_0 + p_0)},$$
 but when analyzing the minority carrier lifetime from

but when analyzing the minority carrier lifetime from external measurements such as Time-resolved photoluminescence (TRPL) the simulations tend to underestimate the radiative lifetime. What needs to be considered is the photon recycling factor; this is where the emitted photon is reabsorbed in the active region of a material

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